					Docket Number (Optional) 11675.76		Application Number 09/6	527.649	
	INFO	RMATION DISCLOSUR	E CITATION		Applicant(s) Sandhu, et al.				
	, Ó	1 Broke Strain smeets of smeets	, <i>,</i>		Filing Date		Group Art Unit	.)	814
:		05 000			July 28, 20	00	ز	2817 -	3//
,	١.	0 6 000		U.S. PAT	ENT DOCUMENTS				
*EXAMINER INITIAL	Ter	DIEST NUMBER	DATE		NAME	CLASS	SUBCLASS		DATE OPRIATE
Th	A	5,445,996	8/95	Kodera	et al.	438	633		
- 141	В	5,486,493	1/96	Jeng		438	623		
TU	C	5,399,235	3/95	Mutsae	rs et al.	438	633		
711	Đ	5,420,075	5/95	Homma	et al.	438	624		
Tli	E	5,599,740	2/97	Jang et	al.	438	626		
TU	F	5,677,239	10/97	Isobe		438	633		
TU.	G	5,795,829	8/98	Shen		438	694		
Ta	H	5,708,303	5,708,303 1/98 Jeng			257	758 <sup>.</sup>		
/				·					
				- •					
7				,					
				FOREIG:	N PATENT DOCUMENTS	}			
-	REF	DOCUMENT NUMBER	- DATE		COUNTRY	CLASS	SUBCLASS	Trans VES	lation NO
j			<u>.</u>						
/					and the second s				
j									
/					-				
	<del></del>			OTHER I	OOCUMENTS (Includin	g Author, Title, D	ate, Pertinent Paj	ges, Etc.)	
TU		M.K. Jain et al., "Adva Low-K Interlevel Diele California, October 199	ctric Architecture:	and Inter s for Capa	connect Systems for UL citance Reduction," Cor	SI Applications oference at Univ	: Homogenous versity of Califo	and Multi rnia, Berk	layer cley,
74	L	Tetsuva Homma, "Fluo Mar Res Soc Symp P	rinated SiO2 Film roc. Vol. 381, pp	s for Inter 239-248.	rlaver Dielectrics in Qua	rter-Micron U	LSI Multilevel l	nterconne	ctions,"
EXAMINE	10	Juah			2/28/0	J			
		If citation considered, whether			ce with MPEP Section 609;	Draw line throu	gh citation if not	in conform:	ance and

Form PTO-A820 (also form PTO-1449)

A green and transported the control of PARTMENT OF COMMERCE

## INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional)
11675.76

Application Number
09/627,649

Applicant(s)
Sandhu, et al.
Filing Date
July 28, 2000

Group Art Unit
28/1

*EXAMINER INITIAL	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)
Tli,	J. Wary et al., "Vacuum-Deposited Parylene AF-4: A Thermally Stable, Low Dielectric Constant Polymer For Interlayer Dielectric Use," DUMIC Conference, pp. 207-213, February, 1996.
ŤōŢ	
i MON O	6 2000 6
TO THI	HIEMARK OF THE STATE OF THE STA
i	
j	
	.;
1	
	· <del></del>
i	

TQuach

2/28/05

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPFP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Docket Number (Optional) Application Number

	11675.76.	09/627.649
** ** *** *** *** *** *** *** *** ***	Applicant(s) Sandhu, et al.	
	Filing Date	Group Art Unit
1 3 2007	July 28, 2000	2814
No.		

ENAMINER: INTHAL	REF	DOCUMENT NUMBER DATE		NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIAT	
TU	1.	6.146.987	11/2000	Wang, et al.	438	618	-	
W	2.	6.177.286	1/2001	Chiddambarrao, et al.	438	14		
								,
							!	
						-		
				·				
						-		
	·····			FOREIGN PATENT DOCUMENT	s			
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
				· ·				
1	[			OTHER DOCUMENTS (Includi	ing Author, Title, D	ate, Pertinent Pay	ges, Etc.)	L

 -		^		 . 1		
	•					
	ļ					
	i					
j						

EXAMINER	TOward	J

28/05

EXXMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609: Draw line through citation if not in conformance an not considered. Include copy of this form with next communication to applicant.

O I P E INFORMATION DISCLOSURE CITATION					Application Number (Optional) Application Number 09/627,649 Applicant(s)				
			sury)		Sandhu, et al				
JUM 5	7 2004	<b>3</b>			Filing Date	roup Art Unit			
		<u> </u>	·		July 28, 200	)O ·	2	814	
VAMINER NAMINER	ADEMAR	<b>*</b> /		U.S. PAT	ENT DOCUMENTS				
NAMINER INTIAL	REF	DOCUMENT NUMBER	UMBER DATE		NAME. CLASS		SUBCLASS	FILING DATE IF APPROPRIATE	
<u> </u>	1.	5,641,382	08/1997	Shih et	al	438	669		
									***************************************
		-			· · · · · · · · · · · · · · · · · · ·				
					,	-			<del></del>
					*****				
							,		
									<del></del> -
				FOREIG:	NPATENT DOCUMENTS	·			
	RLF	DOCUMENT NUMBER	DATE		COUNTRY	CLASS	SUBCLASS		dation
			ļ.—.					VES	NO
·								_ <del>.</del>	
				\					
				OTHERI	OOCUMENTS (Including	Author, Title, D	ate, Pertinent Pag	ges, Etc.1	
						<del>-</del>			
					· <u></u>				
	1	1	•			•			

ENAMINER

Touan

2/28/05

INAMINER: Initial if citation considered, whether or not citation is in conformance with MPLP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.